FTKL03002 (53/53)

Abstract of the Disclosure

An object of the present invention is to form an interlayer insulating film on a substrate and cure the interlayer insulating film in a time shorter than that in the prior art. The present invention is a substrate processing method in which the interlayer insulating film formed on the substrate is irradiated with electron beams in a processing chamber, whereby the interlayer insulating film is cured.

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